## 國立成功大學九十四學年度碩士班招生考試試題

編號: 〒138 系所: 微电子工程研究所

科目:固慧电子元件

- 1. Inside a certain device, electrons with energy 3 eV are incident on a uniform potential energy barrier with 7 eV in height and 1 nm in width. Find the fraction of the electrons that can transmit through this barrier (10%)
- 2. Assume the cube edge of the conventional cell in a fcc lattice is 1 nm. Calculate the surface density of atoms for the (100) plane. (10%)
- 3. Fig. 1 is the band structure of a certain semiconductor. Which curve (A, B, C, or D) is heavy holes? Which curve is light holes? Explain your answer. (10%)

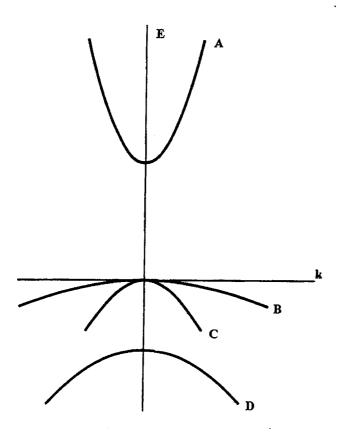


Fig. 1

4. For a silicon at room temperature (kT=0.0259 eV), it doped with 10<sup>15</sup> arsenic atoms/cm³ on one side and doped with 10<sup>16</sup> boron atoms/cm³ on the other side to form an abrupt p-n junction. Calculate the build-in potential, depletion region length for both n and p sides, and also draw the energy band diagram at thermal equilibrium indicating Fermi level, conduction and valence bands for this p-n junction.

(use  $n_i = 10^{10} \, / \mathrm{cm}^3$ , Si dielectric constant 11.8 and permittivity  $\epsilon_0 = 8.85 \mathrm{x} 10^{-14} \, \mathrm{F/cm}$ )

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編號: 万138 系所: 微电子所

科目: 国際电子允许

5. (a) For a P<sup>+</sup>NP device indicate the voltage polarity (+ or -) for the following operation regions: (10%)

Region	V <sub>EB</sub>	$V_{CB}$
Active		
Saturation		
Cutoff		
Inverted active		
Inverted saturation		

- (b) Sketch the minority carrier distribution in P<sup>+</sup>, N, and P regions for an ideal P<sup>+</sup>NP transistor under active mode of operation. (10%)
- 6. For a metal-SiO<sub>2</sub>-Si capacitor having  $N_A$ =5×10<sup>16</sup> cm<sup>-3</sup> and d=8nm, calculate the minimum capacitance on the C-V curve. (Thickness of SiO2 d; dielectric constant of Si 11.9; dielectric constant of SiO<sub>2</sub> 3.9;  $\varepsilon_o$ =8.85×10<sup>-14</sup> F/cm;  $kT/q \sim 0.026$  V, intrinsic carrier density of Si  $n_i$  =9.65×10<sup>9</sup> cm<sup>-3</sup>) (10%).
- 7. Consider a long-channel MOSFET with a channel length  $L=1~\mu\text{m}$ , a channel width  $Z=10~\mu\text{m}$ , substrate doping  $N_A=5\times10^{16}~\text{cm}^{-3}$ ,  $\mu_n=800~\text{cm}^2/\text{V-s}$ , the oxide capacitance per unit area  $C_o=3.45\times10-7~\text{F/cm}^2$ , and the threshold voltage  $V_T=0.7~\text{V}$ . Find the saturation drain voltage and current  $V_{Dsat}$  and  $I_{Dsat}$  for applied gate voltage  $V_G=5\text{V}$ . (20%)